

COMPOSITION AND METHOD FOR PRODUCTION THEREOF, POROUS MATERIAL
AND METHOD FOR PRODUCTION THEREOF, INTERLAYER INSULATING FILM,
SEMICONDUCTOR MATERIAL, SEMICONDUCTOR DEVICE, AND LOW-
REFRACTIVE-INDEX SURFACE PROTECTION FILM

ABSTRACT

Disclosed is a composition comprising a hydrolysate of an alkoxysilane compound, a hydrolysate of a siloxane compound represented by Formula (1), a surfactant, and an element having an electronegativity of 2.5 or less. In Formula (1), R^A and R^B independently represent a hydrogen atom, a phenyl group, $-C_aH_{2a+1}$, $-(CH_2)_b(CF_2)_cCF_3$ or $-C_dH_{2d-1}$, R^A and R^B are not both hydrogen atoms simultaneously, R^C and R^D independently represent a single bond that links a silicon atom and an oxygen atom to form a cyclic siloxane structure, or each independently represent a hydrogen atom, a phenyl group, $-C_aH_{2a+1}$, $-(CH_2)_b(CF_2)_cCF_3$, or $-C_dH_{2d-1}$, a represents an integer of 1 to 6, b represents an integer of 0 to 4, c represents an integer of 0 to 10, d represents an integer of 2 to 4, and n represents an integer of 3 or greater.

(Figure 2)